

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant : Alexander Tregub et al. Art Unit: 1711  
 Serial No.: 10/799,928 Examiner: N. Nutter  
 Filed : March 12, 2004  
 Assignee : Intel Corporation  
 Title : USE OF ALTERNATIVE POLYMER MATERIALS FOR "SOFT"  
           POLYMER PELLICLES

**MAIL STOP AMENDMENT**

Commissioner for Patents  
 P.O. Box 1450  
 Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

Dear Sir:

Applicants call attention to the attached Information Disclosure Statement and documents listed on form PTO-1449.

The documents are in the English language; hence no concise explanation is necessary per Rule 98(a) (3).

Consideration of the foregoing and enclosures plus the return of a copy of the enclosed form PTO-1449 with the Examiner's initials in the left column per MPEP 609 are earnestly solicited along with an early action on the merits.

## CERTIFICATE OF MAILING BY FIRST CLASS MAIL

I hereby certify under 37 CFR §1.8(a) that this correspondence is being deposited with the United States Postal Service as first class mail with sufficient postage on the date indicated below and is addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450.

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Date of Deposit

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*Carol A. Allman*

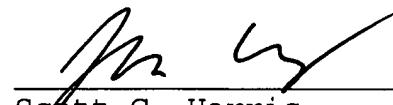
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Kindly accept this Information Disclosure Statement under Rule 97(c) (2). Please apply the rule 17(p) certification fee in the amount of \$180 to Deposit Account No. 06-1050.

Respectfully submitted,

Date: August 4, 2006

  
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**REG. NO. 45,485**

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Substitute Form PTO-1449 (Modified)	U.S. Department of Commerce Patent and Trademark Office	Attorney's Docket No. 10559-895001	Application No. 10/799,928
<b>Information Disclosure Statement</b> by Applicant (Use several sheets if necessary) (37 CFR §1.98(b))		Applicant Alexander Tregub et al.	
		Filing Date March 12, 2004	Group Art Unit 1711

**U.S. Patent Documents**

Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
	AA	2001/0004508	06/2001	Shirasaki			
	AB	2001/0014375	08/2001	Tanaka			
	AC	2002/0136965	09/2002	Tsumoto et al.			
	AD	2002/0179852	12/2002	Zheng et al.			
	AE	2003/0096178	05/2003	Fujita et al.			
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	AI	2005/0045262	03/2005	Eschbach et al.			
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	AK	2005/0203254	09/2005	Tregub et al.			
	AL	4,060,654	11/1977	Quenneville			
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	AO	5,643,654	07/1997	Fujita et al.			
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	AR	6,055,040	04/2000	Sego			
	AS	6,083,577	07/2000	Nakagawa et al.			
	AT	6,111,062	08/2000	Shirota et al.			
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	AW	6,524,754	02/2003	Eynon			
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	AZ	6,652,958	11/2003	Tobita			
	BA	6,822,731	11/2004	Laganza et al.			

Examiner Signature	Date Considered
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EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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		Filing Date <b>March 12, 2004</b>	Group Art Unit <b>1711</b>	

<b>U.S. Patent Documents</b>							
Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
	BB	6,841,312	01/2005	Kalk			
	BC	6,842,227	01/2005	Shu			
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<b>Foreign Patent Documents or Published Foreign Patent Applications</b>							
Examiner Initial	Desig. ID	Document Number	Publication Date	Country or Patent Office	Class	Subclass	Translation
							Yes      No
	BF	0 252 673	01/1988	Europe			
	BG	0 416 528	03/1991	Europe			
	BH	0 438 602	07/1991	Europe			
	BI	0 529 827	03/1993	Europe			
	BJ	0 942 325	09/1999	Europe			
	BK	09-005982	01/1997	Japan			
	BL	2005/022259	03/2005	WIPO			

<b>Other Documents (include Author, Title, Date, and Place of Publication)</b>		
Examiner Initial	Desig. ID	Document
	BM	Chen, et al., "Pellicle-Induced Reticle Distortion: An Experimental Investigation", <i>Proc. of SPIE - The Int'l Soc. for Optical Engineering</i> , Vol. 3546, pp. 167-172 (1998).
	BN	Cotte, et al., "Effects of Soft Pellicle Frame Curvature and Mounting Process on Pellicle-Induced Distortions in Advanced Photomasks", <i>Proc. of SPIE - The Int'l Soc. for Optical Engineering</i> , Vol. 5040, pp. 1044-1054 (2003).
	BO	Cotte, et al., "Experimental and Numerical Studies of the Effects of Materials and Attachment Conditions on Pellicle-Induced Distortions in Advanced Photomasks", <i>Proc. of SPIE - The Int'l Soc. for Optical Engineering</i> , Vol. 4754, pp. 579-588 (2002).
	BP	Cotte, et al., "Numerical and Experimental Studies of Pellicle-Induced Photomask Distortions", <i>Proc. of SPIE - The Int'l Soc. for Optical Engineering</i> , Vol. 4562, pp. 641-651 (2002).
	BQ	Kozeki, T., et al., "Longevity of 193nm/ArF Excimer Pellicle", Mitsui Chemicals, Inc., Pellicle Dept., pp. 1-17 (2001).
	BR	Oshima, et al., "Chemical structure and physical properties of radiation-induced crosslinking of polytetrafluoroethylene", <i>Radiation Physics and Chemistry</i> , vol. 62, pp.39-45 (2001).
	BS	Reu, et al., "Mechanical analysis of hard pellicles for 157 nm lithography", <i>Proc. of the 2001 SPIE Symp. on Optical Microlithography XIV</i> , vol. 4346, 9 pages (2001).

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<b>Other Documents (include Author, Title, Date, and Place of Publication)</b>		
Examiner Initial	Desig. ID	Document
	BT	Shu, et al., "Hard Pellicle Study for 157-nm Lithography", <i>Preprint, to appear in the Proceedings of Photomask Japan</i> , pp. 1-12 (2002).
	BU	Van Krevelen, D.W., with the collaboration of P.J. Hoflyzer, <u>Properties of Polymers, Their Estimation and Correlation with Chemical Structure</u> , Elsevier Scientific Publishing Company, Amsterdam – Oxford – New York, pp. 68-73 (1976).

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